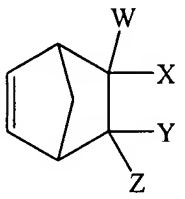
AMENDMENTS TO THE CLAIMS

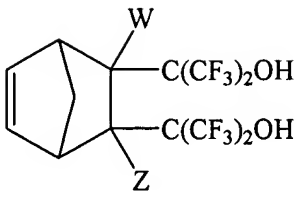
1. (Currently Amended): A compound according to the formula:



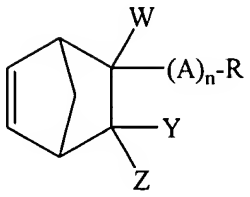
wherein W, X, Y, and Z are independently selected from the group consisting of hydrogen, fluorine, hydroxyl, substituted and unsubstituted alkyl, substituted and unsubstituted fluoroalkyl, provided that: (i) at least one of W, X, Y, and Z is fluorine or a group comprising fluorine, (ii) W, X, Y, and Z are not all the same moiety, (iii) when W and X are both hydrogen, Y and Z are not both hydroxyl, both fluorine, or both alkyl, (iv) when W and Z are both hydrogen or both fluorine, X and Y are not both hydroxyl, (v) when W, X, and Y are all hydrogen, Z is ~~neither~~ not alkyl, ~~nor~~ hydroxyl, or a 1,1-trifluoromethyl-1-hydroxyl moiety having an unsubstituted alkyl chain, (vi) when X and Y are both H, and W is CH_2OH, Z is not C_3F_7 or CF_3; and (vii) when W is hydrogen and X is hydroxyl, Y and Z are not both fluorine.

2. (Currently Amended): ~~A~~ The compound of claim 1 selected from the group consisting of compounds described by the formulae (a)-(c) below:

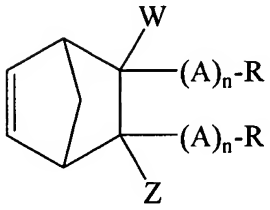
(a)



(b)

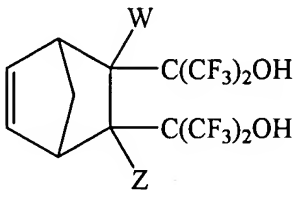


(c)



wherein W, X, Y, and Z are independently selected from the group consisting of hydrogen, fluorine, hydroxyl, substituted and unsubstituted alkyl, substituted and unsubstituted fluoroalkyl; each A is independently CH_2 or CF_2, provided that at least one A is CF_2; each n is independently from about 0 to about 15; and each R is independently hydrogen, fluorine, trifluoromethyl, hydroxyl, or $-C(CF_3)_2OH$.

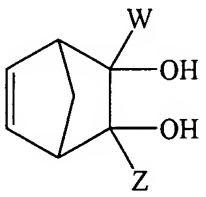
3. (Original): The compound of claim 2 wherein said compound is described by the formula:



wherein W and Z are independently hydrogen or trifluoromethyl.

4. (Original): The compound of claim 3 wherein W and Z are the same moiety.

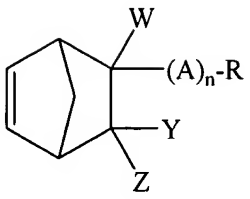
5. (Original): The compound of claim 2 wherein said compound is described by the formula:



wherein W and Z are independently substituted or unsubstituted fluoroalkyl.

6. (Original): The compound of claim 5 wherein W and Z are the same moiety.

7. (Currently Amended): The compound of claim 2 wherein said compound is further described by the formula:



wherein:

W, Y, and Z are independently hydrogen, fluorine, trifluoromethyl, or -$C(CF_3)_2OH$; ~~each~~ A is ~~independently CH_2 or~~ CF_2; each n is independently from about 0 to about 15; and R is hydrogen, fluorine, trifluoromethyl, hydroxyl, or -$C(CF_3)_2OH$.

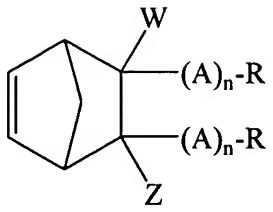
8. (Original): The compound of claim 7 wherein R is -$C(CF_3)_2OH$.

9. (Original): The compound of claim 8 wherein n = 0, and Y and Z are trifluoromethyl.

10. (Original): The compound of claim 7 wherein W and Z are the same moiety selected from the group consisting of hydrogen, fluorine, and trifluoromethyl.

11. (Original): The compound of claim 7 wherein W, Y, and Z are all the same moiety selected from the group consisting of hydrogen, fluorine, and trifluoromethyl.

12. (Currently Amended): The compound of claim 2 wherein said compound is further described by the formula:



wherein:

W and Z are independently hydrogen, fluorine, trifluoromethyl, or $-C(CF_3)_2OH$; each A is independently CH_2 or CF_2; each n is independently from about ~~1~~ 0 to about 15; and each R is independently hydrogen, fluorine, trifluoromethyl, hydroxyl, or $-C(CF_3)_2OH$.

13. (Original): The compound of claim 12 wherein W and Z are the same moiety selected from the group consisting of hydrogen, fluorine, and trifluoromethyl.

14. (Original): The compound of claim 12 wherein the two -(A)n-R groups are both $-(A)n-C(CF_3)_2OH$ groups.

15. (Original): A polymer comprising at least one repeating unit derived from a monomer compound according to claim 1.

16. (Original): The polymer according to claim 15, further comprising one or more repeating units derived from a compound selected from the group consisting of

bicyclo[2.2.1]hept-5-ene-2-(1,1,1-trifluoro-2-trifluoromethylpropan-2-ol) (NBHFA), $CF_2=CF_2$, $CF_2=CH_2$, $CF_2=CFCl$, $CF_2=CHF$, $CF_3CH=CF_2$, $CF_3CH=CHF$, $CF_3CF=CHF$, $CF_3CF=CH_2$, compounds of the formula $R_f(CH_2)_nCXf=CXfYf$ wherein Rf is a perfluoroalkyl group having from about 1 to about 10 carbon atoms, Xf and Yf are indepedently H or F, provided that when Rf is CF_3 and Xf is F, Yf must be H, and mixtures of two or more thereof.

17. (Original): A photoresist composition comprising a polymer according to claim 15.

18. (Original): A photoresist composition comprising a polymer according to claim 16.

19. (Original): The photoresist composition of claim 18 further comprising a solvent and a photoinitiator.

20. (Original): The photoresist composition of claim 19 further comprising a dissolution inhibitor.

21. (Original): The photoresist composition of claim 20 further comprising a sensitizer.

22. (Original): A method for generating a positive tone resist image on a substrate comprising the steps of coating a substrate with a film comprising a photoresist composition of claim 17, exposing the film to radiation, and developing the image.

23. (Original): An integrated circuit assembly comprising a circuit formed by the steps of coating a substrate with a film comprising a photoresist composition of claim 17, exposing the film to radiation, developing the image to expose the substrate, and forming a circuit on the substrate.

24. (Original): An optical wave guide comprising a polymer according to claim 15.

25. (Original): An anti-reflective coating comprising a polymer according to claim 15.

26. (Original): A pellicle comprising a polymer according to claim 15.